

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination MIEHER ET AL.	
		Examiner Gordon J. Stock	Art Unit 2877	Page 1 of 2

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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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		Examiner Gordon J. Stock	Art Unit 2877	Page 2 of 2

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